Abstract

Provided is a target for magnetron sputtering and manufacturing method therefor in which the leakage magnetic flux during magnetron sputtering is kept high without a reduction in the Co content contained in the target, and in which generation of defects such as nodules and particles is unlikely to occur. The present invention comprises: a non-magnetic metal phase containing metal Co and metal Cr with the balance being unavoidable impurities, and having an atomic ratio of the metal Cr to the total of the metal Co and the metal Cr being 25 at% or more and less than 100 at%; and a magnetic metal phase(12) containing metal Co. The volume ratio of the oxide to the non-magnetic metal phase is more than 0 and 1.2 or less. The non-magnetic metal phase and the oxide are mutually dispersed, and no aggregated oxide having a longest diameter of 5 μm or larger is present.